

Title (en)  
ELECTROCHEMICAL DEPOSITION SYSTEM FOR A CHEMICAL AND/OR ELECTROLYTIC SURFACE TREATMENT OF A SUBSTRATE

Title (de)  
ELEKTROCHEMISCHES ABSCHEIDUNGSSYSTEM FÜR EINE CHEMISCHE UND/ODER ELEKTROLYTISCHE OBERFLÄCHENBEHANDLUNG EINES SUBSTRATS

Title (fr)  
SYSTÈME DE DÉPÔT ÉLECTROCHIMIQUE POUR UN TRAITEMENT DE SURFACE CHIMIQUE ET/OU ÉLECTROLYTIQUE D'UN SUBSTRAT

Publication  
**EP 3868923 A1 20210825 (EN)**

Application  
**EP 20158350 A 20200219**

Priority  
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Abstract (en)

The invention relates to an electrochemical deposition system for a chemical and/or electrolytic surface treatment of a substrate, a module for chemical and/or electrolytic surface treatment of a substrate in a process fluid, a use of the electrochemical deposition system or the module for chemical and/or electrolytic surface treatment for a metal deposition application and a manufacturing method for an electrochemical deposition system for a chemical and/or electrolytic surface treatment of a substrate. The electrochemical deposition system comprises an anode, an anode enclosure, and a single electrolyte. The anode enclosure extends at least partially around the anode. The anode enclosure comprises a membrane. The anode and the anode enclosure are arranged in the single electrolyte. The single electrolyte is the only electrolyte of the electrochemical deposition system.

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**C25D 17/001** (2013.01 - KR)

Citation (applicant)  
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• [XI] US 6964792 B1 20051115 - MAYER STEVEN T [US], et al

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TW 202210664 A 20220316; US 2023056444 A1 20230223; WO 2021164894 A1 20210826

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**EP 20158350 A 20200219**; CN 202080076217 A 20200901; EP 2020074266 W 20200901; JP 2022528317 A 20200901;  
KR 20227012156 A 20200901; TW 110115810 A 20210430; US 202017797589 A 20200901